# Characteristic of On-Chip Dipole Antennas Considering Conductive layer on the Surface of Silicon Substrate

<sup>#</sup>Junki Mihira <sup>1</sup>, Takuichi Hirano <sup>2</sup>, Kenichi Okada <sup>3</sup> Jiro Hirokawa <sup>1</sup>, Makoto Ando<sup>1</sup>
<sup>1</sup>Dept. of Electrical and Electronic Eng., Tokyo Institute of Technology S3-19, 2-12-1 O-okayama, Meguro-ku, Tokyo, 152-8552 Japan E-mail : {mihira, jiro, mando}@antenna.ee.titech.ac.jp
<sup>2</sup>Dept. of International Development Eng., E-mail : hira@antenna.ee.titech.ac.jp
<sup>3</sup>Dept. of Physical Electronics, E-mail : okada@ssc.pe.titech.ac.jp

#### Abstract

The EM modeling for silicon substrate was discussed for on-chip dipole antenna. It was found that the effect of Conductive layer is very large and it must be modeled in the EM simulation. The calculated reflection considering Conductive layer is closer to the measured one.

Keywords : On-chip dipole antenna, Millimeter-wave, CMOS substrate, Conductive layer, electromagnetic modeling

## **1. Introduction**

Recent progress in silicon CMOS technology realizes the high speed MOSFET [1]. The CMOS technology can be applied to chips for wireless systems at 60GHz band. On-chip antennas on a CMOS chip are highly desired for mass-production at low cost. It is also important to reduce connection loss between the CMOS chip and the antenna. On-chip antennas have been studied by many researchers [2]-[4]. However, electromagnetic (EM) modeling, especially for the surface of the CMOS chip, has not been investigated well.

In this paper, on-chip dipole antennas are studied by measurement and simulation. There are highly conductive materials on the surface of the silicon substrate of the CMOS chip, such as wells and Conductive layer which are compounds that have silicon and metals. The EM modeling for silicon substrate is discussed in this paper, and the results are compared by measured one.

# 2. Structure of On-Chip Dipole Antenna

Figure 1 shows the structure of the on-chip dipole antenna. The Length of the dipole antenna is L1. A silicon chip is 5mm square and the thickness of silicon substrate is 400  $\mu$ m. Relative permittivity and conductivity of the silicon substrate are 11.9 and 100 S/m, respectively. The thickness of the Conductive layer *t* is very thin, typically around 400 nm up to 1000 nm. The material of metals is aluminum and they are supported by SiO<sub>2</sub> insulator. There is passivation on the top surface of the chip. Figure 2(a) shows the micrograph of the fabricated on-chip dipole antenna with a pad for 100 µm-pitch GSG probe. Figure 2(b) shows the analysis model for Figure 2(a).

#### **3. Results**

The finite element method (FEM) based EM simulator, Ansoft HFSS Ver.11, is used for simulation throughout the paper. The lamped port with  $50\Omega$  internal impedance is used for source modeling.

Figure 3 shows frequency characteristic of reflection coefficient (L1=840 $\mu$ m). Figure 3 (a) shows and the variation of conductivity of Conductive layer when *t*=400 nm. The amplitude of the

reflection becomes larger as the conductivity increases. Typical conductivity of Conductive layer is around  $10 \times 10^4$  S/m, and it is shown that Conductive layer must be considered in EM modeling although it is electrically very thin. The calculated result considering Conductive layer is closer to the measured one. Figure 3 (b) shows and the variation of thickness of Conductive layer when conductivity of Conductive layer is  $10 \times 10^4$  S/m. The amplitude of reflection increases as the thickness of Conductive layer increases. The calculated radiation efficiency without Conductive layer is 0.404% and that with Conductive layer (conductivity:  $10 \times 10^4$  S/m, *t*=800 nm) is 0.025\%.

Figure 4 shows frequency characteristic of reflection coefficient (L1=2200  $\mu$ m). Similar results as Fig. 3 are shown. The calculated radiation efficiency without Conductive layer is 0.277% and that with Conductive layer (conductivity:  $12 \times 10^4$  S/m, *t*=800 nm) is 0.045%.

## 4. Conclusion

The EM modeling for silicon substrate was discussed for on-chip dipole antenna. It was found that the effect of Conductive layer is very large and it must be modeled in the EM simulation. Further verification of EM modeling and radiation characteristic will be studied in future.

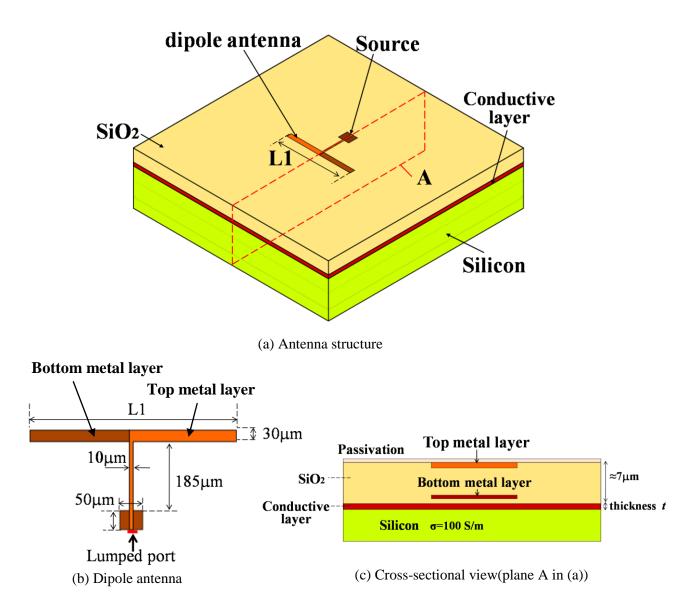
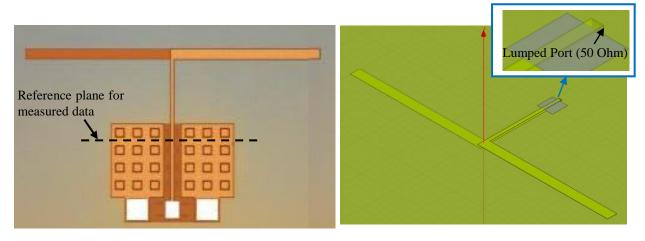


Figure 1: Structure of the on-chip dipole antenna



(a) Micrograph

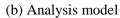
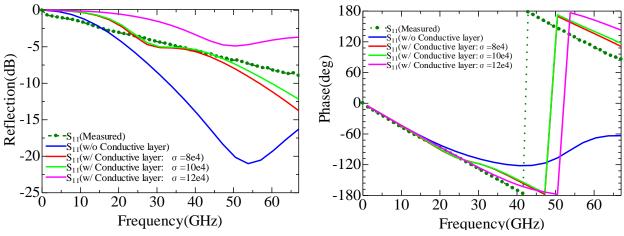
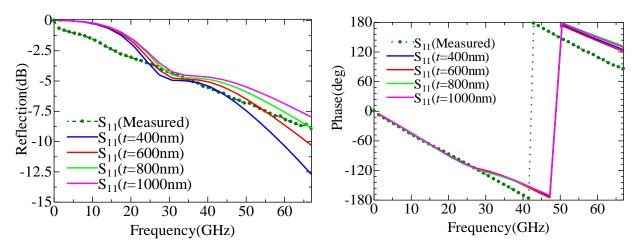


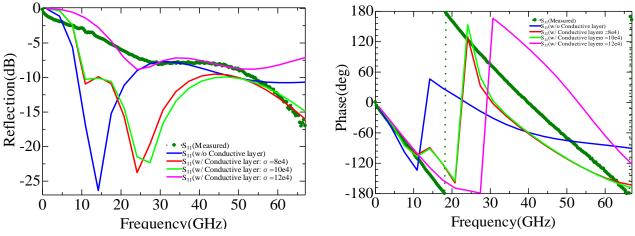
Figure 2: Micrograph and analysis model of the silicon on-chip dipole antenna on a silicon CMOS substrate



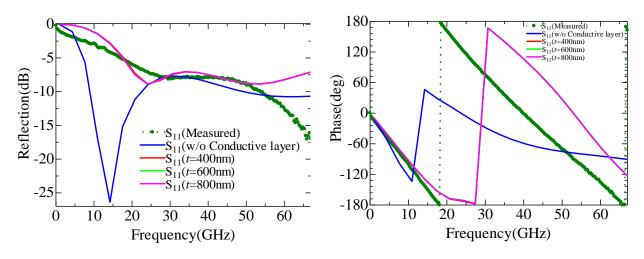
(a) Variation of conductivity of conductive layer (*t*=400 nm)



(b) Variation of thickness *t* (conductivity of conductive layer:  $10 \times 10^4$  S/m) Figure 3: Frequency characteristic of reflection coefficient (L1=840 µm)



(a) Variation of conductivity of conductive layer (*t*=400 nm)



(b) Variation of thickness t (conductivity of conductive layer:  $12 \times 10^4$  S/m)

Figure 4: Frequency characteristic of reflection coefficient (L1=2200 µm)

#### Acknowledgments

This work was partly supported by Semiconductor Technology Academic Research Center (STARC) and VLSI Design and Education Center (VDEC), The University of Tokyo in collaboration with Cadence Design Systems Inc. and ROHM Semiconductor.

#### Reference

- Doan, C.H. et al., "Design considerations for 60 GHz CMOS Radios," Communications Magazine, IEEE., vol.42 No.12, pp.132-140, 2004.
- [2] J. Grzyb et al., "Packaging Effects of a Broadband 60GHz Cavity-Backed Folded Dipole Superstrate Antenna," IEEE AP-S International Symposium 2007, Session: 331.3, pp.4365-4368, June 2007.
- [3] A. Babakhani et al., "mm-Wave Phased Arrays in Silicon with Integrated Antennas," IEEE AP-S International Symposium 2007, Session: 331.4, pp.4369-4372, June 2007.
- [4] S. K. Reynolds et al., "Progress toward a low-cost millimeter-wave silicon radio," in Proc. IEEE Custom Integrated Circuits Conf. (CICC), pp. 563-570, San Jose, CA, USA, Sept. 2005.
- [5] H. Shoki et al., "Millimeter Antenna Technologies to Realize Ultra High Speed Wireless Communication Systems," IEICE Trans.Commun., vol.J90-B, no.09, pp.810-820, 2007.